

## References

1. Deborah D. L. Chung, *Materials for Electronic Packaging*, Butterworth-Heinemann (1995).
2. T. C. S. Vandeuelde, K. Vandierendonek, M. Van Stappen, W. Du Mong and P. Perremans, *Surface & Coating Technology* **113**, 80 (1999).
3. UCFMG, "*Diamond Growth and Films*", Elsevier Science Publishing CO., INC. (1989).
4. M. Kitabatake and K. Wasa, *J. Vac. Sci. Technol.* **A6**, 3 (1998).
5. Yashushi Muranaka, Hisao Yamashita and Hiroshi Miyadera, *Thin Solid Films* **195**, 257 (1991).
6. Kazuhiro Aoyama, Haruo Uyama and Osamu Matsumoto, *J. Electrochem. Soc.* **139**, 2253 (1992).
7. Mansoor Alam, and C. Gomez-Yanez, *IEEE Transactions on Electron Devices* **40**, 1154 (1993).
8. Mitsugu Hanabusa and Kiyohito Tsujihara, *IEEE Journal of Selected Topics in Quantum Electronics* **1**, 848 (1995).
9. R. Manukonda and R. Dillon, *J. Vac. Sci. Technol.* **A 13**, 1150 (1995).
10. J. B. Cui and R. C. Fang, *J. Phys. D: Appl. Phys.* **29**, 2759 (1996).
11. A. N. Obratsov and V. Yu. Timoshenko, *J. Electrochem. Soc.* **143**, 1061 (1996).
12. F. C. Chuang, C. Y. Sun, H. F. Cheng, C. M. Huang and I. N. Lin, , *IEEE*, 299 (1996).
13. Xiaoming He, Wenzhi Li and Hengde Li, *J. Vac. Sci. Technol.* **A 14**, 2039 (1996).
14. Z. Lj. Petrovic, B. Boskovic, A. Jelenak, B. Tomeik, *Thin Solid Films* **304**, 136 (1997).
15. C. Gomez-Aleixandre, M. M. Garcia, O. Sanchez, J. M. Albella, *Thin Solid Films* **303**, 34 (1997).
16. Yunjun Li, Ning Yao, Jintian He, Binglin Zhang and Zhiben Gong, *J. Phys. D: Appl. Phys.* **30**, 2271 (1997).
17. X. L. Peng, T. W. Clyne, *Thin solid films* **293**, 261 (1997).

18. Yaowu Mo, Yiben Xia, Xiaoqin Huang, Hong Wang, *Thin Solid Films* **305**, 266 (1997).
19. J. W. Lee, S. H. Kim, Y. S. Park, M.N. Shinn, D. H. Kang, S. Y. Yoon, D. S. Kim, T. S. Park, S. H. Ha, J. H. Lee and S. J. Kim, *IEEE Transactions on Magnetics* **33**, 826 (1997).
20. P. C. Yang, C. A. Wolden, W. Liu, R. Schlessler, R. F. Davis, J. T. Prater and Z. Sitar, *J. Mater. Res.* **13**, 1120 (1998).
21. Nita Dilawar, Rahul Kapil, Brahampakash, V. D. Vankar, D. K. Avasthi, D. Kabiraj and G. K. Metha, *Thin Solid Films* **323**, 163 (1998).
22. Donald R. Gilbert, Dong-Gu Lee and Rajiv K. Singh, *J. Mater. Res.* **13**, 1735 (1998).
23. Dae-Hwan Kang, Seung-Chul Ha, Ki-Bum Kim, and Seok-Hong Min, *J.Vac. Sci. Technol. A* **16**, 2625 (1998).
24. W. C. Chan, F. Gaspari, T. Allen, P. K. Lim, E. Morano, E. Sagnes, D. Manage, J. Szurmak and S. Zukotynsi, *J.Vac. Sci. Technol. A* **16**, 889 (1998).
25. S. Barrat, P. Pigeat, E. Bauer-Grosse, B. Weber, *Thin Solid Films* **304**, 98 (1997).
26. Fumio Sato, Nobou Saito, Yoshiyuki Hirano, Ahalapitiya H. Jayatissa, Kuniharu Seiji Kawado and Takanori Kato, *J. Vac. Sci. Technol. A* **16**, 2553 (1998).
27. D. Sarangi, O.S. Panwar, Sushil Kumar, P.N. Dixit and R. Bhattacharya, *J.Vac. Sci. Technol. A* **16**, 203 (1998).
28. Jamal Bougdira, Michel Remy, Patrick Alnot, Christian Bruch, Jan K. Kruger, Hassan Chatei, and Jamal Derkaoui, *Thin Solid Films* **325**, 7 (1998).
29. J. Schafer, J. Ristein, S. Miyazaki, L. Loy, *Applied Surface Science* **123/124**, 11 (1998).
30. T. Sato, S. Narumi, S. Ito, K. Akashi, *Thin Solid Films* **316**, 29 (1998).
31. Y. Asakura, K. K. Chattopadhyay, S. Matsumoto and K. Hirakuri, *J.Vac. Sci. Technol. A* **16**, 3185 (1998).
32. P. Andreazza, M. I. De Barros, C. Andreazza-Vignolle, D. Rats, L. Vandenbulcke, *Thin Solid Films* **319**, 62 (1998).

33. M. A. Vesaghi and A. Shafiekhani, *J. Phys. D: Appl. Phys.* **31**, 46 (1998).
34. A. K. Sikder, T. Sharda, and D. S. Misra, D. Chandrasekaram, P. Veluchamy, H. Minoura and P. Selvam, *J. Mater. Res.* **14**, 1148 (1999).
35. D. J. Kester, C. L. Brodbeck, I. L. Singer, A. Kyriakopouloos, *Surface and coating technology* **113**, 268 (1999).
36. Soonil Lee, Seok- Yoon Han and Soo-Ghee Oh, *Surface and Coating Technology* **112**, 194 (1999).
37. M.C. A. Nono, E.j. Corat, M. Ueda, C. Stellati, J. J. Barroso, J. R. Conrad, M. Shamim, P. Fetherston, K. Srintharan, *Surface and Coating Technology* **112**, 295 (1999).
38. T. Grogler, E. Zeiler, A. Franz, O. Plewa, S. M. Rosiwal and R.F. Singer, *Surface and Coating Technology* **112**, 129 (1999).
39. S. Nijhawan, Susan M. Jankovsky, Brian W. Sheldon, *J. Mater. Res.* **14**, 1046 (1999).
40. [www.iaf.fhg.de/diamond/thermics/diamond-thermics.htm](http://www.iaf.fhg.de/diamond/thermics/diamond-thermics.htm)
41. [www.chm.bris.ac.uk/pt/diamond/end.htm](http://www.chm.bris.ac.uk/pt/diamond/end.htm)
42. K. Higaki, et al., *IEEE Transactions on Ultrasonics, Ferroelectrics and Frequency Control* **44**, 1359 (1997).
43. Hoon Jung Jae, et al., *IEEE Transactions On Electron Devices*, **45**, 2232 (1998).
44. Gi Ko Chang, et al., 9<sup>th</sup> International Vacuum Microelectronics Conference, St. Petersburg, 226 (1996).
45. J. A. McLaughline, *Conference of the IEEE Engineering in Medical and Biology Society* **20**, 2879 (1998).
46. [www.bekaert.com/dymonics/coating/eng/fr-deklagen.htm](http://www.bekaert.com/dymonics/coating/eng/fr-deklagen.htm)
47. J. Menard and T. Intrator, *Plasma Sources Sci. Technol.* **5**, 363 (1996).
48. Katsuyuki Okada, Shojiro Komatsu, and Seiichiro Matsumoto, *J. Mater. Res.* **14**, 578 (1999).
49. D. K. Coultas and J.H. Keller, 1990, Europe Patent 0379 828 A2.

50. M. A. Lieberman, A. J. Lichtenberg, *Principle of Plasma Discharges and Material Processing*, John Wiley and Son, Inc, (1994)
51. Richard H. Huddleston, Stanley L. Leonard, *Plasma Diagnostic Techniques*, Academic Press (1965).
52. John H. Keller, *Plasma Sources Sci. Technol.* **5**, 166 (1996).
53. K. Chandrakar, *J. Phys. D: Appl. Phys.* **11**, 1890 (1978).
54. U. Kontshagen, N. D. Grison and J. E. Lawler, *J. Phys. D: Appl. Phys.* **29**, 1224 (1997).
55. I. M. A. El-Fayoumi, *The electrical and electromagnet properties of a low frequency inductively coupled RF plasma source*, Ph. D thesis, The Finders University of South Australia, (1996).
56. Mitsuharu Konuma, "*Film Deposition by Plasma Techniques*", Springer-Verlag, (1992).
57. Brian Chapman, *Glow Discharge Processes, Sputtering and Plasma Etching*, John Wiley and Sons, (1980).
58. E. S. K. Menon and J. Dutta, *J. Mater.*, **14**, 565 (1999).
59. P. K. Bachmann, W. Drawl, D. Knight, R. Wiemer, and R. Messier, *Diamond and Diamond-like Material Synthesis*, Material Research Society, Pittsburgh PA, 1988.